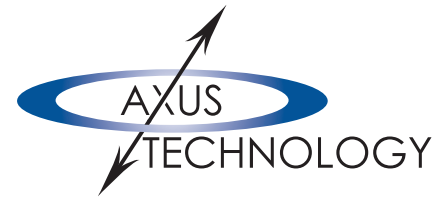


OnTrak DSS 200 Series 2



Your source for leading-edge surface processing solutions



OnTrak DSS 200 Series 2 double-sided PVA scrubber offers production-proven cleaning results for removing slurry particles. Depending on the application, throughputs of 45-65 wafers per hour are attainable, making the DSS-200 Series 2 the most cost-effective wafer cleaning system for wafers from 100mm to 200mm.

The DSS-200 Series 2 can accommodate a wide range of cleaning process applications such as:

- Post-CMP cleaning: oxide, polysilicon, nitride, tungsten, aluminum and copper
- General purpose cleaning: Pre and Post-CVD oxides, post-metallization, surface topography, trench
- Silicon cleaning: prime silicon, reclaim silicon, fab monitor reclaim

STD FEATURES

- 200mm ergonomic load station
- Double sided PVA scrub
- Dual brush boxes
- Dark plastic covers protect light sensitive wafers
- Ammonia dispense
- IR assisted spin dry station
- Robotic unload
- Vertical unload station
- Touchscreen controls



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FEATURES	BENEFITS
<p>Megasonic Option Megasonic transducer mounted on SRD rinse nozzle perpendicular to the wafer surface. High-Frequency system (1-2 MHz) that generates acoustic waves and controlled cavitation providing an enhanced cleaning method while protecting the wafer</p>	<p>Provides an additional cleaning for removing larger surface particles using a non-contact method.</p>
<p>Pressure Vessel for Chemical Distribution 16-gallon (60-liter) capacity Configured with tubing and connectors needed to interface with the chemical system inputs</p>	<p>Fully configured for chemical mixing and easy set up in your fab</p>
<p>Chemical Delivery Upgrade – Single Chemistry Features Through-The-Brush chemical delivery Assembly, Kit, Single Chemistry system</p>	<p>Provides much better and more consistent cleaning results by evenly distributing the cleaning chemistries in the brush. In addition, the constant flow of chemistry and water prevents brush loading.</p>
<p>Chemical Delivery Upgrade – Dual Chemistry Features Through-The-Brush chemical delivery Assembly, Kit, Dual Chemistry system</p>	<p>Enables two cleaning chemistries through the brush modules for maximum production flexibility and provides much better and more consistent cleaning results by evenly distributing the cleaning chemistries in the brush. In addition, the constant flow of chemistry and water prevents brush loading.</p>
<p>Idle D.I. H₂O Conservation/Use Reduction System Upgrade A recirculation and filtration system developed by AT that allows for the use of a fixed amount of DI water for a selected period to significantly reduce the use of DI water during idle time.</p>	<p>Significantly reduces the use of DI water during idle time.</p>
<p>Crystal Grip DSS200 Ontrak cleaner upgrade for handling ultra-thin wafers 300µm and below</p>	<p>Enables sub 300µm thickness wafer handling and fragile wafers without breakage.</p>
<p>Transparent Wafer Sensor Kit 200mm Kit provides specialized sensors to be able to detect clear or semi-clear wafers</p>	<p>Enables reliable detection of 200mm clear glass wafers in a wet environment.</p>
<p>Transparent Wafer Sensor Kit 100mm to 150mm Kit provides specialized sensors to be able to detect clear or semi-clear wafers with flat finder</p>	<p>Enables reliable detection of 100mm and 150mm clear glass wafers in a wet environment.</p>